ABSTRACT

COATING AND DEVELOPING APPARATUS AND METHOD

In one embodiment, a coating and developing apparatus includes a processing block including a vertical stack of early-stage processing unit blocks; a vertical stack of later-stage processing unit blocks disposed laterally adjacent to respective ones of the early-stage processing unit blocks; a vertical stack of developing unit blocks stacked on the early-stage processing unit blocks; a vertical stack of auxiliary processing unit blocks disposed laterally adjacent to respective ones of the developing unit blocks; first transfer units, each of which are disposed between the laterally adjacent early-stage processing unit and later-stage processing unit; second transfer units, each of which is disposed between the laterally adjacent developing unit block and auxiliary processing unit block; and a auxiliary transfer mechanism for transferring a substrate between the first transfer units and between the second transfer units.

Fig. 3

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